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Táto norma obsahuje anglickú verziu európskej normy.
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Táto norma bola oznámená vo Vestníku ÚNMS SR č. 01/14

Obsahuje: EN 62047-18:2013, IEC 62047-18:2013

EUROPEAN STANDARD
NORME EUROPÉENNE
EUROPÄISCHE NORM

EN 62047-18

September 2013

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English version

**Semiconductor devices -
Micro-electromechanical devices -
Part 18: Bend testing methods of thin film materials
(IEC 62047-18:2013)**

Dispositifs à semiconducteurs -
Dispositif microélectromécaniques -
Partie 18: Méthodes d'essai de flexion des
matériaux en couche mince
(CEI 62047-18:2013)

Halbleiterbauelemente -
Bauelemente der Mikrosystemtechnik -
Teil 18: Biegeprüfverfahren für
Dünnschichtwerkstoffe
(IEC 62047-18:2013)

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Comité Européen de Normalisation Electrotechnique
Europäisches Komitee für Elektrotechnische Normung

CEN-CENELEC Management Centre: Avenue Marnix 17, B - 1000 Brussels

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The text of document 47F/155/FDIS, future edition 1 of IEC 62047-18, prepared by SC 47F "Microelectromechanical systems" of IEC/TC 47 "Semiconductor devices" was submitted to the IEC-CENELEC parallel vote and approved by CENELEC as EN 62047-18:2013.

The following dates are fixed:

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NOTE When an international publication has been modified by common modifications, indicated by (mod), the relevant EN/HD applies.

<u>Publication</u>	<u>Year</u>	<u>Title</u>	<u>EN/HD</u>	<u>Year</u>
IEC 62047-6	2009	Semiconductor devices - Micro-electromechanical devices - Part 6: Axial fatigue testing methods of thin film materials	EN 62047-6	2010



IEC 62047-18

Edition 1.0 2013-07

INTERNATIONAL STANDARD

NORME INTERNATIONALE



**Semiconductor devices – Micro-electromechanical devices –
Part 18: Bend testing methods of thin film materials**

**Dispositifs à semiconducteurs – Dispositifs microélectromécaniques –
Partie 18: Méthodes d'essai de flexion des matériaux en couche mince**



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INTERNATIONAL ELECTROTECHNICAL COMMISSION

**SEMICONDUCTOR DEVICES –
MICRO-ELECTROMECHANICAL DEVICES –****Part 18: Bend testing methods of thin film materials**

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International Standard IEC 62047-18 has been prepared by subcommittee 47F: Micro-electromechanical systems, of IEC technical committee 47: Semiconductor devices.

The text of this standard is based on the following documents:

FDIS	Report on voting
47F/155/FDIS	47F/162/RVD

Full information on the voting for the approval of this standard can be found in the report on voting indicated in the above table.

This publication has been drafted in accordance with the ISO/IEC Directives, Part 2.

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SEMICONDUCTOR DEVICES – MICRO-ELECTROMECHANICAL DEVICES –

Part 18: Bend testing methods of thin film materials

1 Scope

This part of IEC 62047 specifies the method for bend testing of thin film materials with a length and width under 1 mm and a thickness in the range between 0,1 μm and 10 μm . Thin films are used as main structural materials for Micro-electromechanical Systems (abbreviated as MEMS in this document) and micromachines.

The main structural materials for MEMS, micromachines, etc., have special features, such as a few micron meter size, material fabrication by deposition, photolithography, and/ or non-mechanical machining test piece. This International Standard specifies the bend testing and test piece shape for micro-sized smooth cantilever type test pieces, which enables a guarantee of accuracy corresponding to the special features.

2 Normative references

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IEC 62047-6:2009, *Semiconductor devices – Micro-electromechanical devices – Part 6: Axial fatigue testing methods of thin film materials*

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